

Chemical Vapor Deposition on Chabazite (CHA) Zeolite Membranes for Effective Post-Combustion CO<sub>2</sub> Capture김은주<sup>1</sup>, 최정규<sup>1,2,†</sup><sup>1</sup>고려대학교 화공생명공학과; <sup>2</sup>고려대학교 그린스쿨(jungkyu\_choi@korea.ac.kr<sup>†</sup>)

Chabazite (CHA) zeolite pores ( $0.37 \times 0.42$  nm<sup>2</sup>) are expected to separate CO<sub>2</sub> (0.33 nm) from larger N<sub>2</sub> (0.364 nm) by recognizing their minute size differences. Furthermore, the hydrophobic siliceous constituent in CHA membranes can allow for maintaining the CO<sub>2</sub>/N<sub>2</sub> separation performance in the presence of H<sub>2</sub>O. In this study, the pore mouth size of all silica CHA (Si-CHA) particles was reduced via the chemical vapor deposition (CVD) of a silica precursor. Accordingly, an increase of the CVD treatment duration decreased the penetration rate of CO<sub>2</sub> into the CVD-treated Si-CHA particles. The CVD process was also applied to siliceous CHA membranes to improve their CO<sub>2</sub>/N<sub>2</sub> separation performance. Compared to the intact ones, the CO<sub>2</sub>/N<sub>2</sub> maximum separation factor (max SF) for CVD-treated CHA membranes was increased by ~2 fold under dry conditions. More desirably, the CO<sub>2</sub>/N<sub>2</sub> max SF was increased by ~3 fold under wet conditions at ~50 °C. The presence of H<sub>2</sub>O in the feed disfavored the permeation of N<sub>2</sub> more than that of CO<sub>2</sub> through CVD-modified CHA membranes and thus, contributed to the increased CO<sub>2</sub>/N<sub>2</sub> separation factor.